

If you'd like more information on the talks:

**"Removal Rate Controlled Ceria Slurries for Low Defectivity and High Planarity in DSTI CMP"**

**Or**

**"Tunable Polysilicon Polishing Slurry Platforms"**

Please contact: James Shen, [James\\_Shen@cabotcmp.com](mailto:James_Shen@cabotcmp.com)